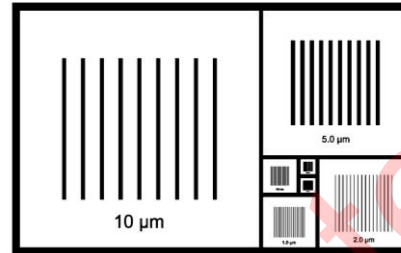
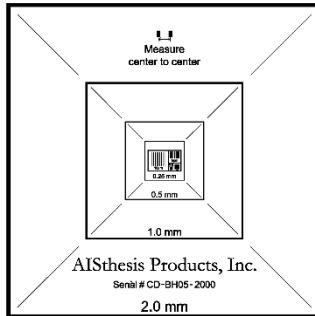


# AISthesis Products

Advanced Imaging Products for Nanotechnology,  
Engineering and Life Sciences  
PO Box 1950, Clyde NC 28721



## Wafer Level Certificate of Traceability for Pelcotec™ Critical Dimension Magnification Standard



**Product Number:** Pelcotec™ 708-01 CDMS-0.1T-ISO-Etched **Customer name and contact information:**

**Product Description:** 2.5x2.5mm, Pelcotec™ 2mm-100nm  
Critical Dimension Magnification Standard



**Wafer Identifier:** CD-BH05

P.O. Box 492477

**As Received Condition:** New

Redding, CA 96049-2477

**As Returned Condition:** N/A

Tel: 530.243.2200

**Date of Receipt:** N/A

[www.tedpella.com](http://www.tedpella.com)

The accuracy of this product with Wafer Identifier CD-BH05 was determined using a Field Emission Scanning Electron Microscope (FE-SEM) by reference comparison to working standards traceable to the National Institute of Standards and Technology (NIST), using CP 01 FE-SEM Imaging of Critical Dimension Magnification Standards (CDMS) and CP 02 Certification of Critical Dimension Magnification Standards. Die were sampled according to method SOP 08 Sampling Die. The data applies only to the CDMS products identified in this report. All results are "as-is". Repair and/or adjustments are not possible.

Below are the average ISO 17025:2017-compliant Certified 10 μm Pitch Measurements unique to Die with Wafer Identifier CD-BH05 and traceable to NIST Certified Standard CD-PG01-0211.

Line	ISO 17025:2017 Compliant Certified Average Pitch on Wafer	Position of Measurement
0-10 μm	9.998 μm	± 7.5 μm from center
10-20 μm	10.000 μm	± 7.5 μm from center
20-30 μm	10.003 μm	± 7.5 μm from center
30-40 μm	10.000 μm	± 7.5 μm from center
40-50 μm	10.002 μm	± 7.5 μm from center
50-60 μm	9.999 μm	± 7.5 μm from center
60-70 μm	10.000 μm	± 7.5 μm from center

70-80 $\mu\text{m}$	9.998 $\mu\text{m}$	$\pm 7.5 \mu\text{m}$ from center
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Average	10.000 $\mu\text{m}$
2-Sigma *	0.0331 $\mu\text{m}$

\* Corrected for sample size using the appropriate Student t-factor.

Measurements are reported with an uncertainty ( $k=2$ )\*\* of  $\pm 0.012 \mu\text{m}$ . Statements of Conformity are not provided in this report. Review the results and verify that they meet the requirements for the intended use. Physical damage to or contamination of the CDMS occurring after calibration may invalidate the reported measurements. Use this product at  $25^\circ\text{C} \pm 5^\circ\text{C}$  and at less than 80% RH.

\*\* Reported uncertainties represent expanded uncertainties expressed at approximately the 95% confidence level using a coverage factor of  $k = 2$ . The reported expanded measurement uncertainty is stated as the standard measurement uncertainty multiplied by the coverage factor K such that the coverage probability corresponds to approximately 95%.

Line	Number of Lines	Position of Measurement	Non-ISO 17025:2017 Compliant Average Measured Distance (first to last line)	Average Pitch of Wafer
2.0 mm	2	$\pm 1.00\text{mm}$ from center	2.00 mm	2.00 mm
1.0 mm	2	$\pm 0.5\text{mm}$ from center	1.00 mm	1.00 mm
0.5 mm	2	$\pm 0.25\text{mm}$ from center	0.500 mm	0.500 mm
0.25 mm	2	$\pm 0.125\text{mm}$ from center	0.250 mm	0.250 mm
5.0 $\mu\text{m}$	12	$\pm 20 \mu\text{m}$ from center	55.01 $\mu\text{m}$	5.00 $\mu\text{m}$
2.0 $\mu\text{m}$	16	$\pm 10 \mu\text{m}$ from center	30.04 $\mu\text{m}$	2.00 $\mu\text{m}$
1.0 $\mu\text{m}$	17	$\pm 5 \mu\text{m}$ from center	16.02 $\mu\text{m}$	1.00 $\mu\text{m}$
500 nm	20	$\pm 4 \mu\text{m}$ from center	9.52 $\mu\text{m}$	501.0 nm
250 nm	21	$\pm 2.5 \mu\text{m}$ from center	5.02 $\mu\text{m}$	250.8 nm
100 nm	52	$\pm 2.5 \mu\text{m}$ from center	5.12 $\mu\text{m}$	100.3 nm

The average pitch is derived from the stated length that was determined using measurements (taken center-to-center) over the stated number of lines (i.e., length divided by the number of lines minus one).

Date of Analysis: January 25<sup>th</sup>, 2024

Equipment used:

Instrument	Model	Serial #	Resolution	Repeatability	Temperature	Humidity	Ref.
FE-SEM	FEI Apreo2	9958357	0.9nm	0.030%	$21.9 \pm 0.1 \text{ }^\circ\text{C}$	$33.3 \pm 0.8\%$	CD-PG01-0211

Location: AlSthesis Products, Inc., PO Box 1950, Clyde North Carolina 28721.

Notes:

D.S. Finch  
Certified by

\_\_\_\_\_  
Signature

H. Haehlen  
Authorized by

\_\_\_\_\_  
Signature

January 25<sup>th</sup>, 2024  
Date report issued.

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P.O. Box 1950, Clyde, North Carolina 28721 Tel: 828.627.6555 E-mail: [CDMS@aistthesisproducts.com](mailto:CDMS@aistthesisproducts.com)

End of report.